## IN THE ABSTRACT

Please cancel the current abstract and insert the following.

~~An exposure apparatus includes an illuminating optics unit for irradiating a reticle, on which a predetermined pattern has been formed, with exposing light emitted from an exposing light source, a reticle stage on which the reticle is placed, a projection optics unit for projecting the predetermined pattern of the reticle onto a substrate, and a substrate stage on which the substrate is placed. The exposure apparatus also includes at least one chamber for internally accommodating the illuminating optics unit, the reticle stage, the projection optics unit and the substrate stage, a first pressure control device for making pressure inside the projection optics unit higher than pressure outside the chamber, and a first correction device for correcting optical characteristics of the projection optics unit in accordance with a value of pressure inside the projection optics unit.~~

-- An exposure apparatus having an illuminating optics unit for irradiating a reticle, on which a predetermined pattern has been formed, with exposing light emitted from an exposure light source, a reticle stage on which the reticle is placed, a projection optics unit for projecting the predetermined pattern of the reticle onto a substrate, and a substrate stage on which the substrate is placed. The apparatus includes at least one chamber for internally accommodating the illuminating optics unit, the reticle stage, the projection optics unit and the substrate stage, a first pressure control device for making a value of pressure inside the at least one chamber higher than a value of pressure outside the at least one chamber, and a first correction device for

correcting optical characteristics of the projection optics unit, by performing at least one of (i) moving an adjustment unit for adjusting the optical characteristics of the projection optics unit and (ii) shifting a wavelength of the exposing light, in accordance with the value of the pressure inside the at least one chamber. --